

| L Number | Hits | Search Text | DB | Time stamp |
|----------|------|---|---|------------------|
| 1 | 31 | <p>(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3))</p> | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:08 |
| 2 | 11 | <p>(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))) not ((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3)))</p> | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:09 |

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| 3 | 4 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (polymethylglutarimide) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:09 |
| 4 | 0 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (napthoquinonediazide or napthoquinonediazido) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:10 |
| 5 | 37 | ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3)) and (heat\$3 or bak\$3) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:10 |

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| 6 | 3 | ((resist or photoresist) and (naphthoquinonediazide or naphthoquinonediazido)) and (novolac or novolak) and dissolution near\$3 accelerat\$3 (430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:16 |
| 7 | 258 | ((("5139904") or ("5747196") or ("6645677") or ("20020187434")).PN. (("20020042029") or ("6040965") or ("5932396") or ("6480355") or ("5747198") or ("6289578") or ("5725997") or ("6483664") or ("6501618") or ("6504678") or ("20010010885") or ("20010019036") or ("20010027029") or ("6465149") or ("20010019465") or ("20010035355") or ("20010038517") or ("20010035343") or ("20020037476") or ("20020071211") or ("20030007295") or ("20020187430")).PN. | USPAT; US-PGPUB USPAT; US-PGPUB | 2004/08/09 18:19 |
| 8 | 4 | | USPAT; | 2004/08/09 18:24 |
| - | 22 | | USPAT; US-PGPUB | 2003/03/18 16:46 |
| - | 61373 | ((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab. | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/03/07 17:59 |
| - | 2793 | ((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/03/07 18:00 |
| - | 2003 | ((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/03/07 19:27 |
| - | 65 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/03/07 19:04 |

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|--|----|--|---|------------------|
| | 23 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 20:07 |
| | 56 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/03/07 19:02 |

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|--|----|---|---|------------------|
| | 33 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) not ((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 20:06 |
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| | | 9 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) not ((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) | USPAT; US-PPGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:57 |
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| | 1938 | <p>(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2")))))</p> | USPAT; US-PPGPUB; EPO; JPO; IBM_TDB | 2003/03/18 16:14 |
| | 1 | ("5872693").PN. | USPAT; | 2003/03/08 15:24 |
| | 2 | <p>(((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (polymethylglutarimide)</p> | USPAT; US-PPGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:54 |

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| | 0 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (napthoquinonediazide or napthoquinonediazido) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:47 |
| | 51 | (resist or photoresist) and (napthoquinonediazide or napthoquinonediazido) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/09/03 13:20 |
| | 3 | ((resist or photoresist) and (napthoquinonediazide or napthoquinonediazido)) and (novolac or novolak) and dissolution near3 accelerat\$3 ("4524121" "4745042" "5252831" "5604073" "5800963").PN. | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/09/03 13:25 |
| | 5 | | USPAT | 2003/03/10 09:27 |
| | 45 | ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/03/10 15:51 |
| | 25 | ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:37 |
| | 216 | 430/328.cccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/03/10 17:38 |
| | 211 | (430/328.cccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (((430/314,316,319-320,328-329).cccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2003/09/03 13:31 |
| | 3 | ("2922855").PN. | USPAT; US-PGPUB; JPO; DERWENT | 2003/09/03 13:52 |

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| | 25 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:30 |
| | 2 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (polymethylglutarimide) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:29 |
| | 54 | (resist or photoresist) and (naphthoquinonediazide or naphthoquinonediazido) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:28 |
| | 3 | ((resist or photoresist) and (naphthoquinonediazide or naphthoquinonediazido)) and (novolac or novolak) and dissolution near3 accelerat\$3 | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:28 |
| | 32 | ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:26 |

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| | 225 | ((430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) ("5721078").PN. | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:19 |
| | 2 | | USPAT; US-PGPUB; JPO; DERWENT | 2003/09/03 13:53 |
| | 244 | ((430/328.ccls. and (heat\$3 or bak\$3) same (expos\$3) same (develop\$3)) not (((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:18 |
| | 33 | ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and (heat\$3 or bak\$3) same (resist or photoresist) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:26 |
| | 3 | ((resist or photoresist) and (naphthoquinonediazide or naphthoquinonediazido)) and (novolac or novolak) and dissolution near3 accelerat\$3 | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:16 |
| | 55 | (resist or photoresist) and (naphthoquinonediazide or naphthoquinonediazido) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:28 |
| | 4 | ((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3)) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (polymethylglutarimide) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:29 |

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|--|----|--|---|------------------|
| | 31 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/04/09 19:31 |
| | 33 | ((430/314,316,319-320,328-329).ccls. and ((oxygen or "O.sub.2") same ((nitrogen or "N.sub.2") and (hydrogen or "H.sub.2")) same (ash\$3 or etch\$3))) and ((heat\$3 or bak\$3) same (resist or photoresist)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:10 |
| | 0 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (naphthoquinonediazide or naphthoquinonediazido)) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:10 |

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| | 4 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) not (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (polymethylglutarimide) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:08 |
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| | 11 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) not ((((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:07 |
| | 31 | (((((magnetic adj head) or (magneto adj resistive) or magnetoresistive or magnetophotoresistive or (magneto adj photoresistive) or (giant adj magneto\$15) or (GMR same magneto\$15)).ti,ab.) and (resist or photoresist or photopolymer\$7 or photoimag\$5)) and ((ash\$3 or (ash adj treat\$4) or etch\$3 or narrow\$3 or shrink\$3 or shrunk\$3 or contract\$3 or small\$3 or littl\$3 or reduc\$3 or decreas\$3 or slim\$4 or trim\$4 or less\$5 or tight\$4) same (resist or photoresist or imag\$3 or pattern\$3))) and ((resist or photoresist or imag\$3 or pattern\$3) same ((oxygen or "O" or "O.sub.2") and (fluorine or fluoride or "F" or "F.sub.2" or ((nitrogen or "N" or "N.sub.2") and (hydrogen or "H" or "H.sub.2"))))) and (((mill\$3 or ion adj beam or FIB or RIE or ion adj etch\$3 or sputter\$3) or (lift adj off or liftoff or remov\$3 or etchback or etch\$3 adj back)) near5 (resist or photoresist or imag\$3 or pattern\$3))) and ((heat\$3 or bak\$3) with (resist or photoresist or imag\$3 or pattern\$3))) | USPAT; US-PGPUB; EPO; JPO; IBM_TDB | 2004/08/09 18:06 |